

TECHNICAL SPEC FOR Ion Implanter

System Model:

Axcelis GSD VHE

- **Wafer size?** 6 inch
- **Wheel type?** Full disk 17 wafers
- **Wafer tilt?** yes
- **Source (i.e. Bernas or IHC)?** bernas
- **Extraction system (i.e. dual bellows)?** Triple axes
- **Gases?** Boron, phosphine
- **SDS Gas box?** yes
- **Max implantation energy (in KeV)?** 5000
- **Max Extraction voltage (in KeV)?** 90
- **Heat Exchanger?** yes

- **Orienter type (flat, notched, etc...)?** flat
- **Hydrogen implantation available? no**
- **Number of trays?**
- **Load and unload locks:** yes
- **Source extraction alignment jig** yes
- **AMU** yes
- **Beamline column** yes
- **Mechanical clamp:** yes
- **Turbo type?**
- **PC type:**
- **Cryo type?**
- **PFS standard or HD?** hd